

EXTRA-THIN FILM OF PHOTOSENSITIVE POLYIMIDE PRECURSOR

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Abstract of JP1245248

PURPOSE: To improve heat resistance and insulating characteristic by developing a polyimide precursor having a specific repeating unit structure on a water surface to form a monomolecular film and accumulating such monomolecular film on a substrate.

CONSTITUTION: The polyimide precursor having the repeating unit expressed by the formula (I) is developed on the water surface to form the monomolecular film and the monomolecular films are accumulated on the substrate. In the formula, X denotes a tetravalence carbon cyclic group expressed by condensed polycyclic arom. rings such as benzene ring, naphthalene ring and anthracene ring; Y denotes a divalence carbon cyclic group; n denotes 8-25 integer; m denotes 0-15 integer. The extra-thin film of the polyimide having the heat resistance and insulating characteristic is thereby obtd.

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